Form 1449 (Modified)	Atty Docket No.	Application No.:
	GENSP014	10/726,802
Information Disclosure	Applicant:	
Statement By Applicant	Kobayashi	
	Filing Date	Group
(Use Several Sheets if Necessary)	December 2, 2003	2181

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub- class	Filing Date
/CKL/	A1.	2004/0049705	03-11-04	Liebenow			09-05-02
	A2.						
	A3.	•					
	A4.						
	A5.						

Foreign Patent or Published Foreign Patent Application

Examiner		Document	Publication	Country or		Sub-		lation
Initial	No.	No.	Date	Patent Office	Class	class	Yes	No
	B1.							
	B2.							
	В3.							
	B4.							
	B5.							

Other Documents

Examiner		
Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1.	
	C2.	
	C3.	
	C4.	

Examiner	/Chun-Kuan Lee/	Date Considered	03/21/2007
İ	/Onun-Ruan Lee/		03/21/2007

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	B3.							
	B4.							
	B5.							

Other Documents

Examiner		
Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
/CKL/	C1.	Examination Report dated November 13, 2006 from related European Patent Application No. 04255609.2.
	C2.	
	C3.	
	C4.	

Examiner	/Chun-Kuan Lee/	Date Considered	03/21/2007

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